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| <b>INFORMATION DISCLOSURE CITATION</b><br><i>(Use several sheets if necessary)</i> | <b>Docket Number (Optional)</b><br><b>TWI-32410</b>       | <b>Application Number</b><br><b>NEW</b> |
|  | <b>Applicant(s)</b><br><b>Abdurrahman Sezginer et al.</b> |   |
|  | <b>Filing Date</b><br><b>HEREWITH</b>                     | <b>Group Art Unit</b><br><b>Unknown</b> |

### U.S. PATENT DOCUMENTS

| *EXAMINER<br>INITIAL | REF | DOCUMENT<br>NUMBER | DATE       | NAME            | CLASS | SUBCLASS | FILING DATE |
|----------------------|-----|--------------------|------------|-----------------|-------|----------|-------------|
| PO                   | AA  | US 2002/0135875    | 09/26/2002 | Niu et al.      | 359   | 564      | 02/27/2001  |
| PO                   | AB  | US 2002/0158193    | 10/31/2002 | Sezginer et al. | 250   | 237      | 02/12/2002  |
| PO                   | AC  | US 2003/0042579    | 03/06/2003 | Schulz          | 257   | 629      | 04/29/2002  |
| PO                   | AD  | US 2003/0043372    | 03/06/2003 | Schulz          | 356   | 327      | 04/29/2002  |
| PO                   | AE  | US 2003/004702     | 03/06/2003 | Schulz          | 430   | 30       | 04/29/2002  |
| PO                   | AF  | 6,532,076          | 03/11/2003 | Sidorowich      | 356   | 630      | 04/04/2000  |

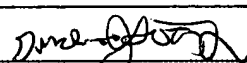
### FOREIGN PATENT DOCUMENTS

|    | REF | DOCUMENT<br>NUMBER | DATE       | COUNTRY | CLASS | SUBCLASS | TRANSLATION |    |
|----|-----|--------------------|------------|---------|-------|----------|-------------|----|
|    |     |                    |            |         |       |          | YES         | NO |
| PO | AG  | WO 02/25723 A2     | 03/28/2002 | PCT     | H01L  | 21/66    |             |    |
|    |     |                    |            |         |       |          |             |    |
|    |     |                    |            |         |       |          |             |    |
|    |     |                    |            |         |       |          |             |    |

### OTHER DOCUMENTS

*(Including Author, Title, Date, Pertinent Pages, Etc.)*

|    |    |  |  |  |  |  |  |
|----|----|--|--|--|--|--|--|
| PO | AH | W. Yang et al., "A Novel Diffraction Based Spectroscopic Method For Overlay Metrology," <i>SPIE's 28th Annual International Symposium and Education Program and Microlithography</i> , February 2003, pp. 9. |  |  |  |  |  |
| PO | AI | T.A. Germer, "Measurement of lithographic overlay by light scattering ellipsometry," <i>Proceedings of SPIE, Surface Scattering and Diffraction and Advanced Metrology II</i> , Vol. 4780, 2002, pp. 72-79.  |  |  |  |  |  |
| PO | AJ | H.T. Huang et al., "Scatterometry-Based Overlay Metrology," <i>SPIE (Microlithography 2003)</i> , Vol. 5038, 2003. 12 pages in length.   |  |  |  |  |  |
| PO | AK | M. Adel et al., "Characterization of Overlay Mark Fidelity," <i>SPIE Meeting on MicroLithography</i> , February 2003, 8 pages in length.   |  |  |  |  |  |

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|--|-----------------------------------|
| <b>Examiner</b><br>   | <b>Date Considered</b><br>3/25/05 |
| <b>Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</b> |                                   |